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N. H. Perr, Y. Tang, M. Grason, and T. O. Mason Northwestern University, Evanston, Illinois 60208, USA appro imation (GGA) are treated in rotationall invariant GGA+U formalism,  $^{13,14}$  ith the onsite Coulomb interaction (*U*) determined in such a a that it correctl reproduces relative stabilit of competing binaries.  $^{15}$  In a supercell approach defect calculation is performed using a 56-atom cubic cell ith 2  $\times$  2  $\times$  2 Monkhorst-Pack  $^{16}$  k points ith kinetic energ cutoff of 300 eV and o gen soft pseudopotentials.

The chemical potential involved is determined using the thermod namic consideration that a compound e ists and all other possible binaries and elemental phases do not e ist under a given gro th condition. Energ of formations are calculated assuming thermod namic equilibrium.

The calculated enthalp of formation includes the corrections<sup>17</sup> due to the image charges, potential alignment, and band lling effects. The dielectric constants necessar in the image charge correction are calculated using the densit functional perturbation approach.<sup>18</sup> The number of defects are calculated b minimizing the Gibbs free energ ith respect to the number of defects assuming formation enthalp is independent of the number of defects. The number of defects depends upon the Fermi energ, hereas the Fermi energ itself depends upon the number of carriers, part of hich are coming from the ionized defects, so e determine self-consistent the defect densit, Fermi energ, and carrier densit requiring overall charge neutralit.

## B. E 5eD5 es a 5 e d

Thin- Im composition gradient samples (libraries-) of Co-Zn-Ni-O ere gro n on 2 in. × 2 in. fused silica glass substrates b rf sputtering from separate targets of CoO, ZnO, and NiO. 19 The sputter sources ere inclined at 30 to the substrate normal to achieve a t o-dimensional (2D) composition gradient. The chamber base pressure as  $10^{-7}$  $10^{-6}$  Torr prior to deposition. Films ere deposited in a 50/50 O<sub>2</sub>/Ar gas mi at a total pressure of 20 mTorr. To cover the full Co<sub>3</sub>O<sub>4</sub>-Co<sub>2</sub>ZnO<sub>4</sub>-Co<sub>2</sub>NiO<sub>4</sub> ternar composition spread, the relative po er on the CoO, ZnO, and NiO sources is varied ith a constant total po er of 150 W. For each librar, the 240min deposition is preceded b a 30-min burn in. Additional, single-composition Co<sub>2</sub>ZnO<sub>4</sub> and Co<sub>2</sub>NiO<sub>4</sub> samples gro n b pulsed laser deposition (PLD) on 100-oriented SrTiO<sub>3</sub> substrates heated to 350 C placed 7 cm from the targets in a chamber ith  $10^{-10}$  atm base pressure lled ith  $2.6 \times 10^{-6}$  atm of o gen ithout addition of argon. Co<sub>2</sub>ZnO<sub>4</sub> and  $Co_2NiO_4$  targets ith Ni/(Ni + Co) = 0.33, 0.38, 0.43 ere ablated using a 248-nm e cimer laser beam ith 2.5 J/cm<sup>2</sup> energ densit and 10 H2 repetition rate.

Materials anal sis focused on measuring a ed set of 44 locations on each substrate in a 4 ro b 11 column format. The electrical, optical, and structural anal sis all focused on the same 44 points on each librar , allo ing for combinatorial anal sis of the results. The ro s ere located 12.5 mm apart and the columns ere 4 mm apart. X-ra uorescence mapping as utilized to measure the relative Co:Ni:Zn atomic ratio and thickness. Sheet resistance values ere characterized ith automated four-point probe mapping. Cr stallinit and phase composition ere measured b -ra diffraction (XRD) in a mapping fashion using a large Bruker diffractometer equipped ith a 2D area detector.<sup>20</sup>

Bulk and po der samples of  $Zn_xCo_{3-x}O_4$  and Mg- and Ni-substituted  $Zn_xCo_{3-x}O_4$  ere fabricated using an aqueous route, in order to mications at an atomic level more rapidl than can be achieved b conventional solid state processing at lo temperatures. For the  $Zn_xCo_{3-x}O_4$  samples, stoichiometric amounts of Co nitrate he ah drate, 99.999%, and Zn nitrate he ah drate, 99.998% (both Alfa Aesar, Ward Hill, MA) ere

The Seebeck coef cient of PLD-gro n  $Co_2ZnO_4$  and  $Co_2NiO_4$  lms as measured at room temperature as detailed in Ref. 24. The Hall effect as measured at room temperature using a Van der Pau method<sup>25</sup> and a variable magnetic eld up to 15 T ith a 1.7-H. $\sigma$  alternating current source using lock-in techniques, and averaging four up-and-do n magnetic eld s eeps of both polarities. The data bet een 0 and 1 T have been removed as the represent purel instrumental noise.

## III. DESIGN AND REALIZATION OF *p*-TYPE TRANSPARENT CONDUCTING OXIDE: THE THREE STEPS

We have applied the three-step inverse design approach to the challenging problem of increasing the hole concentration in *p*-t pe transparent conductors. In particular, rst is the formulation and application of general design principles to select a promising class of materials. Second, high-throughput calculations are used to select the best candidate materials. Then third, further calculations and corresponding e periments are used to verif and optimize the chosen best of class materials. Each of these steps is described in more detail belo

## A. S e5 1: F, 15 a e a6 d a55 de 25 5 15 75 e f, D p- 5 e d 5 36 7

The follo ing four design principles must be achieved in order to create p-t pe transparent conductors.

- (1) Minimize hole killers. For o ide base materials this generall requires a lo concentration (i.e., high formation energ ) of o gen vacancies hich are normall donors (hole killers), as ell as a lo concentration of antisite defects of the high-valent metal on the lo -valent site. If the concentration of potential hole killers is not lo , it is then necessar to design such donor transition levels to be resonant inside the valance band, in hich case the are electricall inactive and so cause no harm to holes even if the are abundant. This latter special case has been recentl termed doping t pe II–.  $^{26}$
- (2) Maximize hole producers. This can imple ma imiting the number (i.e., minimizing the formation energe) of cation

in an octahedral environment. In octahedral s mmetr the  $t_2$  orbitals are nonbonding ith lobes pointing in bet een the o gen ligands, and are thus e pected to ield rather narro sub-bands ith heav mass. In contrast, the e orbitals are bonding and thus e pected to lead to broader bands ith lighter mass. In  $\text{Co}_2\text{ZnO}_4$ , Co is a  $\text{Co}^{3+}$  d6 ion having full occupied spin-up as ell as spin-do n  $t_2$  orbitals. Thus, unfortunatel , the highest occupied state is the nonbonding  $t_2$ .

These considerations are borne out b calculations of the densit of states at the valence band ma imum, sho ing high effective masses (the calculated effective densit of states  $N_v = 2 \times 10^{21}/\text{cm}$ 

J. D. PERKINS et al.	PHYSICAL REVIEW B <b>84</b> , 205207 (2011)
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Figure 5 sho s the predicted hole concentration  $n_h$  (solid line) as a function of Mg content at T=

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<sup>&</sup>lt;sup>2</sup>J. G. Bednor and K. A. Muller, Z. Ph s. B: Condens. Matter